

forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
— forming a first leveling film over the gate wiring;
— forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second leveling film.

2. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first leveling film over the gate wiring;
forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,,
wherein the thickness of the first leveling film is thinner than that of the second leveling film, and
wherein the thickness of the first leveling film is 0.1 μm or more and less than 1.5 μm .

3. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;
forming a first leveling film over the gate wiring;
forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second leveling film, and
wherein the thickness of the second leveling film is from 0.1 μm to 2.9 μm inclusive.

4. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first leveling film over the gate wiring;
forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second leveling film, and
wherein the total thickness of the first leveling film and the second leveling film is from 0.2 μm to 3.0 μm inclusive.

5. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first leveling film over the gate wiring;
forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second leveling film, and

wherein the first leveling film and the second leveling film are insulating films formed by spin coating.

6. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first leveling film over the gate wiring;
forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second leveling film, and
wherein each of the first leveling film and the second leveling film comprises at least one of a polyimide resin, an acrylic resin, a resin containing a siloxane structure, and an inorganic SOG material.

7. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first leveling film over the gate wiring;
forming a second leveling film on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second
leveling film, and
wherein the first leveling film and the second leveling film comprise the same material.

[Please add the following new claims:]

8 (New). A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first leveling film comprising resin over the gate wiring;
forming a second leveling film comprising resin on the first leveling film; and
forming a pixel electrode on the second leveling film,
wherein the thickness of the first leveling film is thinner than that of the second
leveling film.

9 (New). A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring in the gate insulating film;

forming an insulating film comprising an inorganic material over the gate insulating film;

forming a first leveling film over the insulating film;

forming a second leveling film on the first leveling film; and

forming a pixel electrode on the second leveling film,

wherein the thickness of the first leveling film is thinner than that of the second

leveling film.

10 (New). A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

applying a first layer comprising resin by spin coating;

baking the first layer to form a first leveling film;

applying a second layer comprising resin by spin coating;

baking the first layer to form a first leveling film; and

forming a pixel electrode on the second leveling film,

wherein the thickness of the first leveling film is thinner than that of the second

leveling film.

11 (New). A method according to claim 1, wherein the display device is a liquid crystal display device or an EL display device.

12 (New). A method according to claim 1, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

13 (New). A method according to claim 2, wherein the display device is a liquid crystal display device or an EL display device.

14 (New). A method according to claim 2, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

15 (New). A method according to claim 3, wherein the display device is a liquid crystal display device or an EL display device.

16 (New). A method according to claim 3, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

17 (New). A method according to claim 4, wherein the display device is a liquid crystal display device or an EL display device.

18 (New). A method according to claim 4, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

19 (New). A method according to claim 5, wherein the display device is a liquid crystal display device or an EL display device.

20 (New). A method according to claim 5, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

21 (New). A method according to claim 6, wherein the display device is a liquid crystal display device or an EL display device.

22 (New). A method according to claim 6, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

23 (New). A method according to claim 7, wherein the display device is a liquid crystal display device or an EL display device.

24 (New). A method according to claim 7, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, and a computer, a projector.

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